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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/678,830	10/03/2003	John Grunwald	26223-06A	1134
759	08/02/2006		EXAMINER	
John L. Cordani			WILSON, LEE D	
Carmody & Tor	rance LLP			
50 Leavenworth Street			ART UNIT	PAPER NUMBER
P.O. Box 1110			3723	
Waterbury, CT 06721-1110			DATE MAILED: 08/02/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	
	10/678,830	GRUNWALD, JOHN	
Office Action Summary	Examiner	Art Unit	
	LEE D. WILSON	3723	
The MAILING DATE of this communication ap Period for Reply	ppears on the cover sheet w	ith the correspondence ad	Idress
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING D. - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailir earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNION (136(a). In no event, however, may a not will apply and will expire SIX (6) MON te, cause the application to become AB	CATION. reply be timely filed ITHS from the mailing date of this c BANDONED (35 U.S.C. § 133).	
Status			
1) Responsive to communication(s) filed on 2a) This action is FINAL . 2b) This 3) Since this application is in condition for allowed closed in accordance with the practice under the second	is action is non-final. ance except for formal matt	• •	e merits is
Disposition of Claims			
4) Claim(s) 22-26 is/are pending in the application 4a) Of the above claim(s) is/are withdray 5) Claim(s) is/are allowed. 6) Claim(s) 22-26 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/of Application Papers 9) The specification is objected to by the Examination The drawing(s) filled on is/are: a) accompany and applicant may not request that any objection to the Replacement drawing sheet(s) including the correction of th	ewn from consideration. or election requirement. er. cepted or b) objected to e drawing(s) be held in abeyar ction is required if the drawing	nce. See 37 CFR 1.85(a). (s) is objected to. See 37 Cl	
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documen 2. Certified copies of the priority documen 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	nts have been received. Its have been received in A Drity documents have been Bu (PCT Rule 17.2(a)).	pplication No received in this National	Stage
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	Paper No(s	Summary (PTO-413) s)/Mail Date nformal Patent Application (PTC 	O-152)

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Election/Restrictions

1. Applicant's election of Group II, claims 22-26 in the reply filed on 6/22/06 is acknowledged. Because applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 24-25 are rejected under 35 U.S.C. 102(e) as being anticipated by Blalock (7037179).

Blalock teaches claim 24 which has a method a polishing pad (143), forming a pad using radiation to change physical properties (col.5, lines 45-68 and col.6, lines 1-20).

In regard to claim 25 see col 7, lines 5-15.

Claim Rejections - 35 USC § 103

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4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claim 22 is rejected under 35 U.S.C. 103(a) as being unpatentable over Bennett et al (2002/0081956A1) in view of Selvamanickam et al (2004/0132382A1).
 - a. Bennett et al (2002/0081956A1) teaches a method having polishing pad (240), providing a coating of Teflon (see par.44).
 - b. Bennett et al (2002/0081956A1) does not teach an outer surface being at least .05 microns thick.
 - c. Selvamanickam et al. (2004/0132382A1) teaches that a particle size of abrasives or pad thickness of .05 microns is known which allows the polishing pad to be made with that particular thickness.
 - d. It would have been obvious to one having ordinary skill in the art at the time the invention was made to have modified the Bennett et al device by providing the teaching to have a thickness of .05 microns as taught by Selvamanickam et al which allows the polishing pad to be made with that particular thickness since it is a known value.
- 6. Claim 23 is rejected under 35 U.S.C. 103(a) as being unpatentable over Bennett et al (2002/0081956A1) as applied to claim 22 above, and further in view of Ono et al (2004/0055223A1).
 - e. Bennett et al (2002/0081956A1) are discussed above.

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f. Bennett et al (2002/0081956A1) do not teach selecting from a group consisting of dip, spray, spin coating, vacuum metallization, sputtering and electroless plating.

g. Ono et al teach making a polising pad selecting from a group consisting of dip coating and spraying which are used to form polishing pads.

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- h. It would have been obvious to one having ordinary skill in the art at the time the invention was made to have modified the Bennett et al device by providing the teaching to select from a group consisting of dip coating and spraying as taught by Ono et al which are used to form polishing pads.
- 7. Claim 26 is rejected under 35 U.S.C. 103(a) as being unpatentable over Blalock (7037179) in view of Schutz et al (6929539).
 - i. Blalock (7037179) is discussed above.
 - j. Blalock (7037179) does not teach the uses of selecting from a group consisting of electron beam radiation and infrared radiation.
 - k. Schutz et al (6929539) the uses of selecting from a group consisting of electron beam radiation and infrared radiation (col.10, lines 11-15) which is used in cmp polishing with a polishing pad as an alternative radiations sources.
 - It would have been obvious to one having ordinary skill in the art at the time the invention was made to have modified the Blalock (7037179) device by providing the teaching to have use alternative radiation sources such as electron beam radiation and infrared radiation as taught by Schutz et al (6929539).which

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allows the polishing pad to be made with that particular thickness since it is a which is used in cmp polishing with a polishing pad as an alternative radiations sources.

Conclusion

8. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. The 892 form discloses prior art which is being made of record.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to LEE D. WILSON whose telephone number is 571-272-4499. The examiner can normally be reached on M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, JOSEPH HAIL can be reached on 571-272-4485. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Ldw

July 31, 2006

LEE D. WILSON PRIMARY EXAMINED